	Hits	Search Text	DBs
15	170	reticle or photomask or phase\$4shift\$4mask or (alternat\$5 near6 shift\$5 near8 (\$4mask or reticle))) near29 develop\$4) same (strip\$4 or remov\$4 or wash\$4) same (((hard near5 mask) or metal\$4 or conductive or insulat\$4 or dielectric) near9 pattern))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT;
16	486	resist or photosensitive) near12	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
17	49	S15 and S16	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
18	264	pattern\$4)) and (second near8 (photoresist or resist) near12 (layer or form\$3 or film or deposit\$4 or coat\$4) near22 (expos\$4 or irradiat\$4 or illuminat\$4) near36 (trim\$4 or (reduc\$5 near9 (size or width)) or etch\$4) near19 (second near9 (photomask or mask or reticle)) near26 develop\$4)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
19	16	('11)) same (second near8	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
20	588	(first near5 (photoresist or resist or photosensitive) near9 (layer or material or coat\$3 or deposit\$3 or film or form\$3) near22 (expos\$4 or illuminat\$4 or	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
21	79	S20 and S21	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM TDB
22	28	S20 and S21	US-PGPUB
23	21	(photoresist or resist) near12	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
24	8	(photoresist or resist) near12	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
25	14	(photoresist or resist) near12	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB